

<b>Notice of References Cited</b>	Application/Control No. 10/749,878	Applicant(s)/Patent Under Reexamination LEE ET AL.	
	Examiner Bradley K. Smith	Art Unit 2891	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2002/0171107 A1	11-2002	Cheng et al.	257/347
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Epitaxial Growth of TiSi <sub>2</sub> (C49) on (001) Si by Rapid Thermal Annealing" LiMing Wang et al., 10/97, Jpn. J. Appl. Phys. Vol. 36 pp6475-6480.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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